

The Effect of Alcohols on the Anisotropic Etching of Silicon Mary Clare Higgins-Luthman '11 and Dr. Simon Garcia, Department of Chemistry, Kenyon College

Introduction

How can solar cells be more efficient? If the surface of the solar cell is textured, light reflected

from one part of the surface may be absorbed at another.



To the left is an SEM image of a solar cell surface covered with small pyramids. (Papet 2006)

Can a textured surface be created using chemical reactions? Anisotropic etching causes small pyramids to form during etching.



•Longer carbon chains decrease (110) etch rate •Methanol and ethanol have similar pKas but ethanol changes the (110) etch rate and methanol does not. •A 3-carbon chain decreases the (110) etch rate the most.

Back View of Silicon Wedge





Before etching, the pattern consists of a circular array of 180 silicon wedges.

Results



1,2- ethanediol	83.1	14.77
1,3- propanediol	35.0	15.1
1,4- butanediol	28.0	15.1

•Bifunctional ligands follow the same pattern as monofunctional ligands.

•However, the etch rate does not decrease as much as with monofunctional ligands.

Methods



Etching for 30 minutes causes the wedges to retract, giving rise to a "flower pattern."

Steric Hindrance: Increasing the Number of Carbons at the Hydroxyl Group (110) (100) 30% KOH 30% KOH with 0.5 M ethanol 30% KOH with 0.5 M ethanol 30% KOH with 0.5 M tert-butanol						
0 20 40 60 80 100 120 140 160 degrees a Orientation (degrees)						
Alcohol	Structure	(110) Etch Rate	рКа	M		
ethanol		31.6	15.9	bi ca		
2-propanol		23.5	17.1	de		
tert-butanol		31.9	18	F •\ اiؤ •\		

•2-propanol has a larger pKa, but decreases the (110) etch rate more than ethanol.

•The(110) etch rate does not follow a clear trend when steric hindrance is increased.

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The pattern is unwrapped to reveal a plot of etch rate vs. orientation.

Vhy should pKa Matter?

- Alkoxide is thought to be the reactive species of the gand.
- ower pKa = Higher concentration of alkoxide
- Higher concentration of alkoxide = Slower removal of con
- Ka of a typical alcohol is between 14-18
- oH of etchant solution is 14.83

ummary

hanging the ligand has little effect on the (100) urface. Several ligands decreased the (110) surface tch rate. These ligands slow down the removal of toms from the (110) surface. Ligands with a larger umber of carbon atoms tend to have a larger effect. 1onofunctional alcohols are more effective than ifunctional alcohols with the same number of arbon atoms. pKa does not effect the (110) etch rate ecrease.

Further questions

What effect does changing the concentration of the igand have on the (110) surface etch rate? What ligands change the (100) etch rate?

Acknowledgements